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RASIRC to Present at Surface Preparation and Cleaning (SPCC) Conference

Describes application of novel reactive chemistry sources for surface passivation

San Diego, Calif – April 14, 2016 –RASIRC today announced that Chief Technology Officer Dan Alvarez, PhD will present at the upcoming [Surface Preparation and Cleaning Conference](#). The presentation titled “*Novel Reactive Chemistry Sources for Surface Passivation of Future Generation Channel Materials*” will be presented April 20 in the Beyond CMOS session. The conference , held April 19-20, 2016 in Santa Clara, California, focuses on developments and challenges in advanced wafer and mask cleaning and surface preparation technologies.

The RASIRC presentation will focus on new *in situ* gas phase cleaning and passivation methods for new channel materials that will allow better carrier confinement and mobility. An approach will be described that involves the transfer of substrate dangling bonds to silicon and subsequently functionalized with an oxidant or nitriding agent. Challenges associated with traditional oxidants and promising new chemistries will be discussed. Test results for new delivery techniques for water free hydrogen peroxide and hydrazine will also be covered.

“Novel Gate Stack materials and High Aspect Ratio structures require gas phase treatment, but traditional oxidants and nitriding sources require too much heat and are too aggressive. This created a need for new reactive chemistries,” said Jeffrey Spiegelman, RASIRC President and Founder. “BRUTE hydrogen peroxide and BRUTE hydrazine deliver a safer solution for surface treatment at the atomic interface.”

For more information, request a copy of the presentation. Additional information is also available for [BRUTE™ hydrogen peroxide](#) and [BRUTE™ hydrazine](#).

About RASIRC

RASIRC specializes in products that generate and deliver gas to fabrication processes. Each unit is a dynamic gas plant in a box—converting common liquid chemistries into safe and reliable gas flow for most processes. First to generate ultra-high purity steam from de-ionized water, RASIRC technology can now also deliver hydrogen peroxide and hydrazine gases in controlled, repeatable concentrations. RASIRC gas delivery systems, humidifiers, closed loop humidification systems, and steam generators are critical for many applications in semiconductor, photovoltaic, pharmaceutical, medical, biological, fuel cell, and power industries. Call 858-259-1220, email info@rasirc.com or visit <http://www.rasirc.com>.

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